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	Application No.	Applicant(s)	٦
	10/786,901	AMOS ET AL.	ı
Notice of Allowability	Examiner	Art Unit	٦
	Asok K. Sarkar	2891	
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.			
1. X This communication is responsive to <u>amendment filed 1//3 2006</u> .			
2. The allowed claim(s) is/are 1-19.			
3. ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) ☐ All b) ☐ Some* c) ☐ None of the: 1. ☐ Certified copies of the priority documents have been received.			
2. Certified copies of the priority documents have been received in Application No			
3. Copies of the certified copies of the priority documents have been received in this national stage application from the			
International Bureau (PCT Rule 17.2(a)).			
* Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application. THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.			
4. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.			
5. CORRECTED DRAWINGS (as "replacement sheets") must be submitted.			
(a) including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached			
1) hereto or 2) to Paper No./Mail Date			
(b) including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date			
Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d).			
6. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.			
Attachment(s) 1. ☐ Notice of References Cited (PTO-892)	5. ☐ Notice of Informal F	Patent Application (PTO-152)	
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. Interview Summary	(PTO-413),	
3. ⊠ Information Disclosure Statements (PTO-1449 or PTO/SB/	Paper No./Mail Da 08), 7. ⊠ Examiner's Amend	ite ment/Comment	
Paper No./Mail Date <u>9/05 and 12/05</u> 4. ☐ Examiner's Comment Regarding Requirement for Deposit		ent of Reasons for Allowance	
of Biological Material	9. 🗌 Other		

DETAILED ACTION

Response to Amendment

1. Applicant's explanation of the instant invention in pointing the difference with the cited prior art was found to be persuasive.

EXAMINER'S AMENDMENT

- 2. In view of the allowable subject matter, the Applicant's attorney was contacted for canceling the withdrawn claims.
- 3. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Leslie S. Szivos on January 30, 2006.

The application has been amended as follows:

Claims 20 – 52 have been cancelled.

Allowable Subject Matter

- 4. Claims 1 19 are now allowed.
- 5. The following is an examiner's statement of reasons for allowance:

Claims 1 – 19 recite, inter alia, a process for fabricating a complementary metal oxide semiconductor (CMOS) structure comprising the steps of providing a plurality of polySi gates overlying a semiconductor substrate, each polySi gate comprises a dielectric cap located on an upper surface thereof wherein said dielectric cap comprises

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a first dielectric material, forming silicided source/drain regions in the semiconductor substate, forming a dielectric stack on the semiconductor substrate, wherein said dielectric stack comprises a first lower dielectric laver and a second upper dielectric layer, wherein the first lower dielectric layer comprises the first dielectric material and wherein the second upper dielectric laver comprises a second different dielectric material, planarizing the dielectric stack to remove an upper portion of the second upper dielectric layer performing an etching process to selectively remove the first lower dielectric laver and the dielectric cap against the second upper dielectric laver to thereby expose only an upper surface of each polySi gate wherein the exposed upper surface of each polySi gate is below an upper surface of the second upper dielectric layer and performing a salicide process which converts each polySi gate to a metal silicide gate, wherein each metal silicide gate has substantially the same height, is composed of the same silicide phase, and has substantially the same workfunction for the same polySi ion implant conditions. The art of record does not disclose or anticipate the above limitation in combination with other claim elements nor would it be obvious to modify the art of record so as to form a device including the above limitation.

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Conclusion

6. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

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7. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Asok K. Sarkar whose telephone number is 571 272 1970. The examiner can normally be reached on Monday - Friday (8 AM- 5 PM).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, William B. Baumeister can be reached on 571 272 1722. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

8. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

ASOK K. Sarkar January 30, 2006

Primary Examiner